

**Amendments to the Claims:**

This listing of claims will replace all prior versions, and listings, of claims in the application:

**Listings of Claims:**

1. (currently amended) A semiconductor die package comprising;  
a semiconductor die;  
a leadframe having a chemically-etched surface; and  
a capsule comprising a molding compound, said capsule enclosing at least a portion of said die and at least a portion of said leadframe, said molding compound being in contact with said chemically-etched surface of said leadframe so as to reduce the possibility of separation between said molding compound and said leadframe as said package undergoes thermal cycles and/or to inhibit the ingress of moisture into said package.
2. (original) The semiconductor package of Claim 1 wherein said leadframe consists essentially of copper alloy.
- 3-6. (canceled)
7. (currently amended) A semiconductor package comprising:  
a semiconductor die;  
a leadframe having a chemically-etched surface; and  
a capsule enclosing at least a portion of said die and at least a portion of said leadframe;  
said package further comprising an organo-metallic coating on the surface of the leadframe.
- 8-20. (canceled)
21. (previously presented) The semiconductor package of Claim 1 wherein the arithmetic mean deviation of a profile of said chemically-etched surface is in the range of 0.050  $\mu\text{m}$  to 0.170  $\mu\text{m}$ .

22. (previously presented) The semiconductor package of Claim 21 wherein the mean peak-to-valley height of said chemically-etched surface is in the range of 0.180  $\mu\text{m}$  to 0.700  $\mu\text{m}$ .

23. (previously presented) The semiconductor package of Claim 22 wherein the ten-point height of irregularities of said chemically-etched surface is in the range of 0.400  $\mu\text{m}$  to 1.500  $\mu\text{m}$ .

24. (previously presented) The semiconductor package of Claim 21 wherein the ten-point height of irregularities of said chemically-etched surface is in the range of 0.400  $\mu\text{m}$  to 1.500  $\mu\text{m}$ .

25. (previously presented) The semiconductor package of Claim 24 wherein the maximum profile valley depth of said chemically-etched surface is in the range of 0.200  $\mu\text{m}$  to 0.750  $\mu\text{m}$ .

~~26~~27. (currently amended) The semiconductor package of Claim 22 wherein the maximum profile valley depth of said chemically-etched surface is in the range of 0.200  $\mu\text{m}$  to 0.750  $\mu\text{m}$ .

27. (previously presented) The semiconductor package of Claim 21 wherein the maximum profile valley depth of said chemically-etched surface is in the range of 0.200  $\mu\text{m}$  to 0.750  $\mu\text{m}$ .

28. (previously presented) The semiconductor package of Claim 1 wherein the mean peak-to-valley height of said chemically-etched surface is in the range of 0.180  $\mu\text{m}$  to 0.700  $\mu\text{m}$ .

29. (previously presented) The semiconductor package of Claim 28 wherein the ten-point height of irregularities of said chemically-etched surface is in the range of 0.400  $\mu\text{m}$  to 1.500  $\mu\text{m}$ .

30. (previously presented) The semiconductor package of Claim 29 wherein the maximum profile valley depth of said chemically-etched surface is in the range of 0.200  $\mu\text{m}$  to 0.750  $\mu\text{m}$ .

31. (previously presented) The semiconductor package of Claim 28 wherein the maximum profile valley depth of said chemically-etched surface is in the range of 0.200  $\mu\text{m}$  to 0.750  $\mu\text{m}$ .

32. (previously presented) The semiconductor package of Claim 1 wherein the ten-point height of irregularities of said chemically-etched surface is in the range of 0.400  $\mu\text{m}$  to 1.500  $\mu\text{m}$ .

33. (previously presented) The semiconductor package of Claim 32 wherein the maximum profile valley depth of said chemically-etched surface is in the range of 0.200  $\mu\text{m}$  to 0.750  $\mu\text{m}$ .

34. (previously presented) The semiconductor package of Claim 1 wherein the maximum profile valley depth of said chemically-etched surface is in the range of 0.200  $\mu\text{m}$  to 0.750  $\mu\text{m}$ .

35. (canceled)

36. (new) The semiconductor package of Claim 7 wherein the capsule is in contact with the organo-metallic coating so as to reduce the possibility of separation between said capsule and said leadframe as said package undergoes thermal cycles and/or to inhibit the ingress of moisture into said package.

37. (new) The semiconductor package of Claim 1 wherein a recess is formed in the leadframe, a surface of the leadframe within the recess being chemically-etched.

38. (new) The semiconductor package of Claim 1 comprising a plated metal layer on a portion of the leadframe.

39. (new) The semiconductor package of Claim 38 wherein a surface of the leadframe under the plated metal layer is chemically-etched.

40. (new) The semiconductor package of Claim 38 wherein a surface of the leadframe under the plated metal layer is not chemically-etched.

41. (new) The semiconductor package of Claim 1 wherein a top surface or a side surface of said leadframe is chemically-etched and a bottom surface of said leadframe is not chemically-etched.

42. (new) The semiconductor package of Claim 1 wherein said chemically-etched surface is light brown to brown in color.

43. (new) The semiconductor package of Claim 7 wherein the arithmetic mean deviation of a profile of said chemically-etched surface is in the range of 0.050  $\mu\text{m}$  to 0.170  $\mu\text{m}$ .

44. (new) The semiconductor package of Claim 7 wherein the mean peak-to-valley height of said chemically-etched surface is in the range of 0.180  $\mu\text{m}$  to 0.700  $\mu\text{m}$ .

45. (new) The semiconductor package of Claim 7 wherein the ten-point height of irregularities of said chemically-etched surface is in the range of 0.400  $\mu\text{m}$  to 1.500  $\mu\text{m}$ .

46. (new) The semiconductor package of Claim 7 wherein the maximum profile valley depth of said chemically-etched surface is in the range of 0.200  $\mu\text{m}$  to 0.750  $\mu\text{m}$ .

47. (new) The semiconductor package of Claim 23 wherein the maximum profile valley depth of said chemically-etched surface is in the range of 0.200  $\mu\text{m}$  to 0.750  $\mu\text{m}$ .